



Form 1449 (Modified) Information Disclosure Statement By Applicant (Use Several Sheets if Necessary)	Atty Docket No.	Application No.:
	LAM1P152 P0692	09/782,446
	Applicant:	
	HO et al.	
Filing Date	Group	
February 12, 2001	1746	

U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A						
	B						
	C						
	D						
	E						
	F						
	G						
	H						
	I						

Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
	J							
	K							
	L							
	M							
	N							

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
LV	O	U.S. Patent Application Serial No. 09/782,185, entitled "Unique Process Chemistry for Etching Organic Low-K Materials", filed February 12, 2001
LV	P	U.S. Patent Application Serial No. 09/782,678, entitled "Post-Etch Photoresist Strip with O2 and NH3 for Organosilicate Glass Low-K Dielectric Etch Applications", filed February 12, 2001
LV	Q	U.S. Patent Application Serial No. 09/782,437, entitled "Use of Hydrocarbon Addition for the Elimination of Micromasking during Etching of Organic Low-K Dielectrics", filed February 12, 2001
Examiner		Date Considered
LV		11 / 12 / 2002

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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1746**U.S. Patent Documents**

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
LV	A	6,037,255	03/14/00	Hussein et al.	438	675	05/12/99
	B	6,080,529	06/27/00	Ye et al.	430	318	10/19/98
	C	6,153,511	11/28/00	Watatani	438	623	06/25/99
	D	6,174,796	01/16/01	Takagi et al.	438	622	12/30/98
LV	E	6,194,128	02/27/01	Tao et al.	430	313	09/17/98
	F						
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	Q	
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LAM VINH	2/12/2002	

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